

ABSTRACT

A resist polymer solution comprising a resist polymer containing a repeating unit decomposed by the action of an acid so as to be soluble in alkali and a repeating unit
5 having a polar group, the resist polymer dissolved in a solvent for coating film formation, wherein the amount of impurities whose boiling point is not higher than that of the solvent for coating film formation is 1 mass% or less based on the resist polymer. Further, there is provided a process for producing a resist polymer solution, comprising the step (1) of redissolving a solid matter containing a resist polymer in a solvent for
10 coating film formation (a) and/or a solvent (b) whose boiling point at atmospheric pressure is not higher than that of the solvent (a); and the impurity removing step (2) of distilling off the solvent (b) and/or any excess amount of solvent (a) in vacuum from the redissolution solution obtained in the step (1).